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# 3  
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8-11-92

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

CHEN, et al.

Serial No.: 07/863,791

Filed: April 6, 1992

For: METHOD FOR IMPROVED  
LITHOGRAPHIC PATTERNING IN A  
SEMICONDUCTOR FABRICATION  
PROCESS

Examiner

Art Unit:

RECEIVED  
AUG 05 1992  
GROUP 450

INFORMATION DISCLOSURE STATEMENT

Commissioner of  
Patents and Trademarks  
Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. § 1.97(b), and in compliance with Rule 37 C.F.R. § 1.56, Applicant hereby submits a copy of Information Disclosure Statement Form PTO-1449 together with a copy of the documents cited on that form.

It is respectfully requested that the cited documents be considered and that the enclosed copy of Information Disclosure Statement Form PTO-1449 be initialled by the Examiner to indicate such consideration and returned to Applicant

The references are:

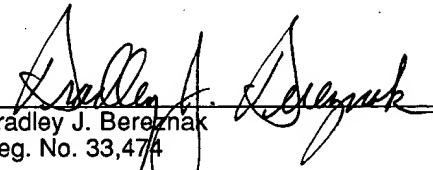
- (1) White, L. K.; "Contact Hole Imaging in Stepper Lithography", pgs. 1-8, SPIE Vol. 733 Optical Lithography VI (1987).
- (2) Ito et al.; "Submicrometer Pattern Correction for Optical Lithography" pgs. 9-17, SPIE Vol. 922 Optical / Laser Microlithography (1988).
- (3) Starikov, A.; "Use of a Single Size Square Serif for Variable Print Bias Compensation in Microlithography: Method, Design, and Practice", pgs. 34-46, SPIE Vol. 1088 Optical / Laser Microlithography (1989).

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Respectfully submitted,

BLAKELY, SOKOLOFF, TAYLOR & ZAFMAN

Date: 7/22, 1992

  
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